## Modeling and Simulation of IC-Fabrication Steps

A survey of the activities at the Technical University Vienna will be presented. Efficient simulation tools and accurate modeling are necessary to keep pace with the increasing complexity of IC-fabrication techniques. the 1-dim and 2-dim process simulators ZOMBIE present PROMIS. permit in an easy way the exchange of These programs physical models and quantities of interest. ZOMBIE has especially been designed for the improvement and development of new models (e.g. phosphorus diffusion, field-enhanced diffusion The major advantage of ZOMBIE versus PROMIS lies in the significantly more efficient computer resource utilization due to the fact that only one space dimension is considered. Therefore model evaluation and comparison to (1-dim) measurements PROMIS carried out much quicker. the 2-dim version of is ZOMBIE. This program can simulate the mentioned physical dimension which exceeds by far the capabilities of in two existing process simulators. Tupical applications and like the simulation of oxidation enhanced be presented diffusion, various models of gold diffusion in silicon in interaction between intrinsic point defects silicon and dopants during diffusion. Both programs permit the results of measurements or prior simulations to be the initial solution for further simulations. The results of one- and two-dimensional Monte-Carlo simulations of ion implantations in crystalline and amorphous material, which have started at our University, can easily connected to all process and therefore be simulations. A secure numerical environment is necessary for the models since critical domains in space and development of new simulation can often not be estimated time during the in Fully adaptive spatial and transient grid for the advance. simulation are therefore implemented into the simulation tools. These features free the user from many numerical aspects of simulation and reduce CPU-time and memory requirements.